

Title (en)

METHOD FOR ELECTRODEPOSITING A DARK CHROMIUM LAYER ON A SUBSTRATE AND SUBSTRATE HAVING AT LEAST ONE SIDE FULLY COVERED WITH A DARK CHROMIUM LAYER

Title (de)

VERFAHREN ZUM GALVANISCHEN ABSCHIEDEN EINER DUNKLEN CHROMSCHICHT AUF EINEM SUBSTRAT UND SUBSTRAT MIT MINDESTENS EINER VOLLSTÄNDIG MIT EINER DUNKLEN CHROMSCHICHT BEDECKTEN SEITE

Title (fr)

PROCÉDÉ DE DÉPÔT ÉLECTROLYTIQUE D'UNE COUCHE DE CHROME SOMBRE SUR UN SUBSTRAT ET SUBSTRAT AYANT AU MOINS UN CÔTÉ ENTIÈREMENT RECOUVERT D'UNE COUCHE DE CHROME SOMBRE

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Abstract (en)

[origin: WO2022123019A1] The present invention relates to a method for electrodepositing a dark chromium layer on a substrate and a substrate having at least one side fully covered with a dark chromium layer. The method includes utilizing an aqueous trivalent chromium electroplating bath comprising colloidal particles and a step of treating the substrate with a rinse liquid having a temperature of 50°C or more.

IPC 8 full level

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